

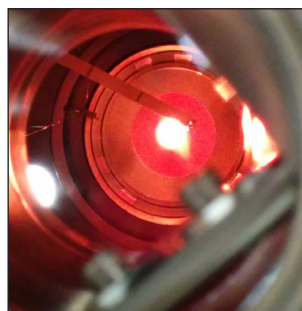


Pushing the Limits of R&D

Veeco Nova ULTRA High Temperature Substrate Heater

Proven Performance at >1850°C

Push your research to new limits with Veeco's Nova™ ultra-high temperature substrate heater. Our novel design allows customers to reach temperatures and new growth regimes inaccessible a few years ago. This heater is capable of 1850°C thermocouple temperature and can heat a full 3" wafer. The hot zone, constructed entirely of refractory metals, ensures clean operation in ultra-high vacuum. Additionally, an integrated water cooling enclosure thermally isolates the heater, minimizing the impact to the rest of the chamber. These features make the Nova heater ideal for "hot" research areas including graphene, novel nitride, and boron nitride applications.



Optical view of Veeco's Nova heater with platen



Veeco's new Nova heater model rendition



Features:

- Proven performance at >1850°C
- Full 3" wafer
- Special graphite and tungsten platens for various substrate sizes
- Field serviceable filaments
- 0-30 rotations per minute speed
- Water-cooled enclosure
- Available exclusively on Veeco's GENxplor® R&D MBE System

For the latest research achievements conducted with this product, check out the paper from the researchers at the University of Nottingham: "High temperature MBE of graphene on sapphire and hexagonal boron nitride flakes on sapphire"